# <u>Operation of the electron beam for external off-</u> axis injection, electron beam seeding and hosing in AWAKE Run 2b (2023-2025)

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#### Nikita Z. van Gils

# In Run 2b the 19 MeV electron beam has been used for ...

#### Seeding of the self-modulation II. Seeding of the beam-hose (hosing) instability III. External injection of electrons into wakefields







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#### Electron production: illumination of Cs<sub>2</sub>Te photo cathode with a UV laser pulse













#### Input beam characterisation: transverse emittance and bunch charge measurement

Electron production: illumination of Cs<sub>2</sub>Te photo cathode with a UV laser pulse













Input beam characterisation: transverse emittance and bunch charge measurement

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# New screens enable beam measurements inside of the vapour source

For the first time, AWAKE is able to:

- 1) Align the electron beam to the proton beam trajectory (in vacuum) within the vapour source
- 2) Ensure overlap (crossing) of electron bunch trajectory with the plasma and proton bunch trajectory in vacuum
- 3) Maximise electron bunch charge density at z<sub>e</sub> → screens enable transverse beam size measurements and tuning of optics and waist location
  4) Set and record the electron bunch injection angle θ<sub>i</sub> (by using also a second screen upstream of the waist location)







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# Seeding of self-modulation and hosing



# Seeding of the <u>self-modulation</u> (SM) and <u>hosing process</u>

For this the electron beam should be:

- shorter than  $\lambda_{pe}$ : used 200 pC  $\rightarrow$  ~3 ps rms length
- focused at the entrance of the vapour source
- of symmetric transverse distribution (see next slide)













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- focused at the entrance of the vapour source
- <u>of symmetric transverse distribution (see next</u> slide)

### Seeding of SM:

 aligned on the proton bunch trajectory (on axis) using YAG +0.5m and YAG +1.5m

### Seeding of hosing:

• induced by (parallel) transverse displacement of the proton bunch w.r.t. the electron bunch (as was done in Tatiana's work) => See Michele's talk





# Alignment challenges

Non-symmetric transverse distributions on YAG +1.5m:

• Difficult to determine beam centre due to large horizontal beam size (due to dispersion), tails and multiple maxima (which one should we align to..?)











on the fit.

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# Acceleration experiments



## External off-axis injection of witness particles External injection ? $\rightarrow$ relatively low amplitude wakefields (~0.5 GV/m) of high phase velocity (relativistic factor $\gamma \sim \gamma_{p+} \sim 427$ )



# External off-axis injection of witness particles

External injection ?  $\rightarrow$  relatively low amplitude wakefields (~0.5 GV/m) of high phase velocity (relativistic factor  $\gamma \sim \gamma_{p+} \sim 427$ )

Off axis injection ?  $\rightarrow$  and several meters into the vapour source at a position (ze ~ 1-6m), to avoid the loss of witness particles due to wakefield phase shifts occurring during SM or from the density step  $\rightarrow$  this requires flexibility of the setup to be able to focus the beam meterwise along the vapour source



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# Electron witness beam setups used for acceleration experiments (2024)

Site of injection is set to be == focal point of electron bunch

Beam waist at 1.5m

Charge: 400pC or 800pC Max injection angle ~7mrad









A IV-A-K-E

- Two most common configurations

Beam waist at 5.5m

Charge: 400pC or 800pC Max injection angle ~1.2mrad







# Electron witness beam setups used for acceleration experiments (2024)

Two most common configurations

Site of injection is set to be == focal point of electron bunch

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Charge: 400pC or 800pC Max injection angle ~7mrad

> Maximum injection angle without significant beam losses at the entrance aperture









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Beam waist at 5.5m

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Beam waist at 1.5 m

Charge: 400 pC Injection angle ~7 mrad Measurement on YAG +1.5m

Site of injection is set to be == focal point of electron bunch

Beam waist at 5.5 m

Charge: 400 pC Injection angle ~1.2 mrad Measurement on YAG +5.5m

Dashed horizontal lines: plasma skindepth for plasma electron density of 2e14 Red circle: proton bunch  $1\sigma$  contour











# Measurement of the electron beam waist location

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2σ<sub>x, y</sub> [mm]

Beam waist at 1.5m

#### Charge: 400pC Max injection angle ~7mrad



Charge: 400pC Max injection angle ~1.2mrad









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# Electron beam centroid position jitter at focus (for 400 pC and 800 pC bunches used in acceleration experiments)

Beam centroid and sizes calculated using Gaussian fits to the hor. / ver. projections

Beam waist at 1.5m

For 400 pC  $< \frac{90}{4}$  µm with a beam size of 500/420 µm For 800 pC < 105 µm with a beam size of 690/770 µm

Beam waist at 5.5m

For 400 pC  $< 85 \mu$ m with a beam size of 650/580  $\mu$ m For 800 pC  $< 105 \mu m$  with a beam size of 770/700  $\mu m$ 







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Α	W

ocus	Charge [	pC]	Sig_x [mm]		Sig_y [mm]		Cent jitter
1.5m	200		0.441± 0.023		$0.349 \pm 0.01$	(0.051,	
1.5m	400		<mark>0.498</mark> ± 0.022		<mark>0.418</mark> ± 0.047		(0.090,
1.5m	800		<mark>0.687</mark> ± (	0.045	<mark>0.768</mark> ± 0.05	58	(0.102,
ocus	Charge [pC]	Si	g_x [mm]	S	big_y [mm]		Centre Jitter [r
5.5m	200	0.4	11 ± 0.022	2 0.5	513 ± 0.043		(0.043, 0
5.5m	400	<mark>0.6</mark>	<mark>50</mark> ± 0.080	) <mark>0.</mark>	<mark>582</mark> ± 0.050		(0.081, 0
5.5m	800	<mark>0.7</mark>	<mark>64</mark> ± 0.098	3 <mark>0.</mark>	<mark>693</mark> ± 0.059		(0.101, 0



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#### Beam waist at 5.5m

For 400 pC  $< 85 \mu$ m with a beam size of 650/580  $\mu$ m For 800 pC  $< 105 \mu m$  with a beam size of 770/700  $\mu m$ 

Conclusion: electron beam position jitter smaller than the transverse beam size

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Α	W

ocus	Charge [	pC]	Sig_x [mm]		Sig_y [mm]		Cent jitter
1.5m	200		0.441± 0.023		$0.349 \pm 0.01$	(0.051,	
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# Adjusting electron beam timing (w.r.t laser pulse)

- Commonly needed for acceleration studies to investigate the wakefields along the proton bunch. Adjustment range: ~ [50, 600] ps
- For seeding/hosing: close to the laser pulse (~ 0ps)









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Proton bunch rms length ~200ps Electron bunch rms length ~ 2-5ps





# Adjusting electron beam timing (w.r.t laser pulse)

- UV pulse is derived from main laser pulse
- RF system and booster structure timing are synched with the main laser pulse
  - <=> Change electron beam delay
  - <=> Delay UV pulse on cathode
  - <=> Adjust RF phase to compensate

=> These adjustments may change the electron beam alignment











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--> Scanned delay stage over its travel range for different charges and observed that: • Centroid position shifts < centroid position jitters for all cases

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Scanned delay stage over its travel range for different charges and observed that:
Centroid position shifts < centroid position jitters for all cases</li>

→ Conclusion: adjustment of the electron beam timing does not compromise its alignment







Delay [ps]



# **Deleterious effects (I)**

- The current in the spectrometer magnets (dipole and quadrupole doublet) are commonly varied during acceleration studies (see Fern's talk)
- It was observed that this directly affects the alignment • of the injection beam at the injection location











### **Deleterious effects**

- The current in the *spectrometer* magnets (dipole and quadrupole doublet) are commonly varied during acceleration studies (see Fern's talk)
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- Measurements (Figures on the RHS) show beam position changes for a 400pC beam, focused at +5.5m. The beam position changes on the mm-scale >> c/w<sub>pe</sub>!











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Electron beam alignment is checked after every current change and prior to taking the next measurement











# **Deleterious effects (II)**

- The electron beam position on the BPMs showed significant "jumps" (black line), matching the SPS magnet ramping frequency (~every 20s) (green line)
- This was also observed on the beam screen after the first vertical dispersive element of the line (of lower magnitude (red line)
- At the focal point (here on the screen 5.5m into the vapour source) these jumps are within beam centroid jitters (blue line)

NB: Only vertical displacements at the site of injection are plotted since injection occurs in the horizontal plane



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- Most of the time this effect was not observed at the injection location.
  - If they were observed  $\rightarrow$ alignment performed with extraction events only.

NB: Only vertical displacements at the site of injection are plotted since injection occurs in the horizontal plane



- millimetres.
- the heaters off.

Before

Centroid jumps of ~ 1.5mm!



# **Deleterious effects (thrice)**



During SPS extraction, the electron beam position was observed to shift by several

• Some vapor source heaters remained on during extraction, though they should be off before beam arrival. This issue was resolved by adjusting the trigger timing, that turns

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- the heaters off.

Before

Centroid jumps of ~ 1.5mm!



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A WAKE

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#### After

Typical beam centroid jitters ~100 microns





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# Summary and Conclusions

Different experiments require large flexibility of the e-beam setup in terms of:

•Beam waist position (different locations along the vapour source) •Alignment (on axis: SM and hosing; off-axis: probing wakefield amplitudes)

The addition of YAG screens inside the vapour source allows for the verification of :

- electron and proton beam alignment for seeding of SM and hosing as well as external injection of witness particles to probe wakefields
- electron beam optics up to and around focus
- solvable through clear and concise procedures







• and determination, and mitigation of any external factors and their effect on the

electron bunch (position and shape) => which may compromise experiments =>





#### Thank you for listening!







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#### The End



#### Backup slides















Focus	Charg	Sig_x	Sig_y	Centroid jitter	Focu s	Charge	Sig_x	Sig_y	Centroid jitter	Foc us	Charg e	Sig_x	Sig_y	Centr
	е				1.5m	200pC	0.441±	0.349±	(0.051, 0.042)mm	5 5m	200n	0 411+	0 513+	(0.043
0.5m	200pC	0.386±	0.295±	(0.030,			0.023mm	0.017mm	(01001) 010 12)	0.011	C	0.022mm	0.043mm	(0.040,
		0.019mm	0.024mm	0.032)mm	1.5m	400pC	0.498±	0.418±	(0.090, 0.075)mm	5.5m	400p	0.650±	0.582±	(0.081,
0.5m	400pC	0.668±	0.519±	(0.047,			0.022mm	0.047mm			С	0.080mm	0.050mm	
		0.055mm	0.020	0.036)mm	1.5m	800pC	0.687± 0.045mm	0.768± 0.058mm	(0.102, 0.097)mm	5.5m	800p	0.764±	0.693±	(0.101,
											U	0.0301111	0.0091111	

Errorbars are variations in beam size and error on the fit. Centroid jitters over 100 1Hz events.



#### Focus at iris beamsizes measured on BTV54, BTVEXPVOL and CAM1



Focus	Charge	Sig_x	Sig_y	Centroid jitter
0.5m	200pC	0.386± 0.019m m	0.295± 0.024mm	(0.030, 0.032)mm
0.5m	400pC	0.668± 0.055m m	0.519± 0.020	(0.047, 0.036)mm

Errorbars plotted are variations in beam size and error on the fit.

#### <u>Electron beam setup:</u>

 Electron creation: illuminating a Cs\_2Te cathode with a UV laser pulse (typical spot size: ~1mm, average energy: ~200nJ, top hat intensity profile).



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#### Electron beam setup:

- Electron creation: illuminating a Cs\_2Te cathode with a UV laser pulse (typical spot size: ~1mm, average energy: ~200nJ, top hat intensity profile).
- These bunched electrons are then accelerated to an energy of ~5MeV in an S-band RF-photo-injector.
- Two low-energy solenoids located after the photo-injector focus the electrons inside the 1m-long travelling wave booster structure, where they are further accelerated to ~19MeV, and hand them over to the transfer line.
- Charge can be varied between 100-800 pC (measured at a Faraday cup)



RF-photoinjector













#### <u>Electron beam setup:</u>

- the first beam screen (BTV)
- the beam out of the gun is matched to the beam line (Vittorio Bencini)
- numerical optimisation







- is set at the location of injection
- (MADX tracking) beam sizes















#### Bunch length, normalised emittance and charge as a function of RF gun phase



![](_page_45_Figure_4.jpeg)

#### <u>Phase shifter 1105, WG 342, 0mm</u>

Charge	Emittance mm*mrad	Length p
<mark>lris 300</mark> 375pC	(3.70, 2.74)	4.22± 1.14
Iris 200 325pC	(2.86, 2.71)	3.64±1.1
Iris min 275pC	(2.68, 2.44)	3.15± 1.28
Iris min with OD+0.3: 250pC	(2.65, 2.17)	2.87±1.1
Iris 400: 650pC	(4.81, 5.45)	4.63±0.77

![](_page_46_Picture_3.jpeg)

4

![](_page_46_Figure_6.jpeg)

#### Bunch length and normalised emittance as a function of charge; phase fixed; timing fixed after realignment

![](_page_47_Figure_1.jpeg)

certain momentum).

![](_page_47_Picture_4.jpeg)

![](_page_47_Picture_5.jpeg)

### Estimation of injection angle and limitations for large ze

e.g. take 2mm (two standard deviations) wide beam. In order to not have cutting at entrance => max offset 7mm (red line), 5mm max offset for beams max 4mm wide (pink line)

#### <u>Angles assuming straight line trajectories</u> (0.5m-4.5m)

Wide possibility of injection angles; can cover up to 4.5m with same angle (max up to 5mrad for z=0.5m,1.5m and 2.5m) then below 2.5mrad.

![](_page_48_Picture_4.jpeg)

![](_page_48_Picture_5.jpeg)

![](_page_48_Picture_6.jpeg)

![](_page_48_Picture_8.jpeg)

![](_page_48_Figure_9.jpeg)

![](_page_48_Picture_10.jpeg)

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e.g. take 2mm (two standard deviations) wide beam. In order to not have cutting at entrance => max offset 7mm (red line), 5mm max offset for beams max 4mm wide (pink line)

#### Angles assuming straight line trajectories (4.5m-9.5m)

Narrower choice, very flat injection angle up to possibly 1.2mrad for all; however not guaranteed.

Also raises the problem of entering the plasma column before the point of injection e.g. the offset would be 1mm (~radius plasma column) 1m prior e.g. for 9.5m and this does not take beamsize into account (may enter even earlier)

![](_page_49_Picture_5.jpeg)

![](_page_49_Picture_6.jpeg)

![](_page_49_Picture_7.jpeg)

![](_page_49_Picture_9.jpeg)

![](_page_49_Figure_10.jpeg)

![](_page_49_Picture_11.jpeg)

- 2.1

- 1.5

- 0.6

- 0.3

![](_page_50_Figure_0.jpeg)

![](_page_50_Picture_1.jpeg)

![](_page_50_Picture_2.jpeg)

![](_page_50_Picture_3.jpeg)

![](_page_50_Picture_5.jpeg)

![](_page_50_Picture_7.jpeg)

![](_page_50_Picture_9.jpeg)

#### Electron beam seeding images XMPP

![](_page_51_Figure_1.jpeg)

#### 2e14, 3e11, 200pC, XMPP

![](_page_51_Picture_3.jpeg)

#### A WAKE

![](_page_51_Figure_5.jpeg)

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![](_page_51_Figure_7.jpeg)